

10/369086

JO rec'd PCT/PTO 05 FEB 2002

INFORMATION DISCLOSURE STATEMENT BY APPLICANT	ATTY. DOCKET NO. 10901/36	SERIAL NO. To be assigned
	APPLICANT WEIDMANN et al.	
	FILING DATE Herewith	GROUP 287Z To be assigned

U. S. PATENT DOCUMENTS

EXAMINER INITIAL	PATENT NUMBER	PATENT DATE	NAME	CLASS	SUBCLASS	FILING DATE*
<i>JD</i>	4,536,650*	Aug. 20, 1985	Carena et al.	250	231.14	—
<i>JD</i>	4,644,156**	Feb. 17, 1987	Takahashi et al.	216	24	—

* - If pertinent

* Cited in the attached German Search Report (copy enclosed).

** Copy of reference is not enclosed because reference is cited in Search Report (copy of reference provided by International Searching Authority).

FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
<i>JD</i>	40 06 789	Sept. 5, 1991	Germany			NO Abs., *	
<i>JD</i>	34 17 176	Nov. 21, 1985	Germany			NO Abs., *	
<i>JD</i>	34 16 864	Nov. 21, 1985	Germany			NO Abs., *	
<i>JD</i>	32 19 917	Dec. 23, 1982	Germany			NO Abs., *	
<i>JD</i>	0 240 776	Oct. 14, 1987	Europe			NO Abs., *	
<i>JD</i>	43 20 728	Jan. 12, 1995	Germany			NO **	
<i>JD</i>	0 511 597	Nov. 4, 1982	Europe			**	
<i>JD</i>	0 849 567	Jun. 24, 1998	Europe			NO **	
<i>JD</i>	2 072 850	Oct. 7, 1981	Europe			**	

* Cited in the attached German Search Report.

** Copy of reference is not enclosed because reference is cited in Search Report (copy of reference provided by International Searching Authority).

OTHER DOCUMENTS

EXAMINER INITIAL		AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.
<i>JD</i>	—	Zubel, I. et al., "Silicon anisotropic etching in alkaline solutions I. The geometric description of figures developed under etching Si(100) in various solutions," Sensors and Actuators A, vol. 70, no. 3, 1998, pp. 250-259.**
<i>JD</i>	—	Zubel, I. et al., "Silicon anisotropic etching in alkaline solutions II. On the influence of anisotropy on the smoothness of etched surfaces," Sensors and Actuators A, vol. 70, no. 3, 1998, pp. 260-268.**

** Copy of reference is not enclosed because reference is cited in Search Report (copy of reference provided by International Searching Authority).

EXAMINER <i>Zahm Zubel</i>	DATE CONSIDERED 6 DEC 2004
EXAMINER: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT	ATTY. DOCKET NO. 10901/36	SERIAL NO. 10/069,086
	APPLICANT J. Weidmann et al.	
	FILING DATE July 8, 2002	GROUP 2877 2872

U. S. PATENT DOCUMENTS

EXAMINER INITIAL	PATENT NUMBER	PATENT DATE	NAME	CLASS	SUBCLASS	FILING DATE

FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO

OTHER DOCUMENTS

EXAMINER INITIAL		AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.
<i>JS</i>	—	Petersen, Kurt E., "Silicon As A Mechanical Material", Proceedings of the IEEE, U.S., IEEE, NY, Bd. 70, No. 5, May 1, 1982, pp.420-457*

* Listed in International Search Report (copy not provided, copy provided by International Searching Authority).

EXAMINER <i>Zahn Zuba</i>	DATE CONSIDERED 6 DEC 2004
EXAMINER: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	

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